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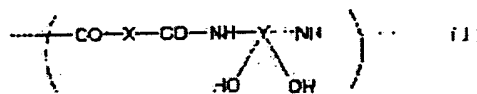
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(54) POLYBENZOXAZOLE PRECURSOR, PHOTSENSITIVE RESIN COMPOSITION AND ELECTRONIC PART

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a polybenzoxazole precursor whose i-line transmission is good and can form the polybenzoxazole having a low relative dielectric constant and high thermal resistance, to provide a photosensitive resin composition using the same, and to provide an electronic part using the same.

SOLUTION: This polybenzoxazole precursor has repeating units represented by the general formula (1) (X is a divalent organic group; Y is a tetravalent organic group; two or one of X and Y have adamantane structures in the main chains). The photosensitive resin composition and the electronic part each uses the polybenzoxazole precursor.



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